

AMENDMENTS TO THE SPECIFICATION

IN THE SPECIFICATION:

Please replace the paragraph beginning on page 7, line 7 with the following paragraph:

Referring to FIG. 3A, compensating elements  $R_0 \sim R_2$  achieve the object of voltage compensation by adjusting the whole resistance value of the resistance elements  $R_h$ . Basically, the resistance of  $R_0$  is higher than the resistance of  $R_1$  and further higher than the resistance of  $R_2$ . That is, the high resistance is compensated at the both ends having lower resistance but the low resistance is compensated at the middle having higher resistance. By doing so, the different resistance values caused by serially connecting different amount of the resistance elements  $R_h$  within each section can be thoroughly uniformed. As shown in FIG. 3B, the structure of the compensating elements in one of preferable embodiment in accordance with the present invention is illustrated. The compensating elements  $R_0 \sim R_2$ , basically, are formed on the indium-tin oxide (ITO) layer coated on a glass substrate via an etching process. As having the same height  $h$  and the width of  $R_2$  being wider than the width of  $R_1$  and further wider than the width of  $R_0$ , the resistance of  $R_2$  is less than the resistance of  $R_1$  and further less than the resistance  $R_0$  since the resistance value is inversely proportional to the width of the conductive wire. By doing so, the object of uniforming the resistance value of the resistance element within each section can be achieved. Wherein, the geometric pattern of the compensating

elements  $R_0 \sim R_2$  is a rectangle in the present embodiment (It is noted that the geometric pattern of the compensating elements should not be only limited to rectangle). Moreover, the relationships between the sizes of the compensating elements  $R_0 \sim R_2$  and the interval distances among thereof are shown in Formula 1 as following:

$$LCn = ( ( n * ( ( DA / LA ) * RG + RL ) * C ) / DB ) - LC0 \dots$$

(Formula 1)

where n represents the compensated section number, LCn represents the compensated width of the  $n^{\text{th}}$  section (unit: inch), DA represents the line distance of each section of silver paste (unit: inch), LA represent the contact length between each section of silver paste and ITO (unit: inch), RG represent the glass surface resistance ~~(unit: ohm)~~ (unit: ohm/inch<sup>2</sup>), RL represents the line resistance of each section of silver paste ~~(unit: ohm)~~ (unit: ohm/inch), C represents an adjust constant (about 45.3, depending on the resistance of substrate), DB represents the distance of silver paste pattern (unit: inch), and LC0 represents the width (a known value) of the  $0^{\text{th}}$  section (unit: inch).

Please add the following paragraph beginning on page 8, line 22:

These dimensions and the arrangement of the elements can be more clearly seen in Fig. 5A. The distance DA is the length of an individual section of compensating elements, including one half of

the interval between the element and the adjoining compensating element on each side. The distance LA is the length of the original silver paste section for each compensating element. The compensated width LCn is shown as 540 and is the silver paste pattern which remains after the etching process which removes 540' of each section. The distance of the silver paste pattern of the compensating elements from the resistance elements is DB and thus is the distance in the vertical direction shown in Fig. 5A between 540 and resistance elements 530.

Please replace the paragraph beginning on page 8, line 23 with the following paragraph:

For example, when the compensated width in the 0<sup>th</sup> section is 30 (0.03 inches), the compensated width in the fifth section is ~~48~~ 480 (0.48 inches). The calculating process is shown in Formula 2 as below:

$$LC5 = ((5*((0.02/0.73)*500+2.5)*45.3)/7.19)-30 = 480 \dots(\text{Formula 2})$$

where the data listed above is only the preferable data in the present embodiment, however the data should be modified or adjusted to meet the practical material in order to get the perfect compensation effects.

Please replace the paragraph beginning on page 12, line 6 with the following paragraph:

The plurality of compensating elements 540 are spaced along the perimeter edges of the uniform resistive surface 520, wherein the sizes of them and the intervals between each others are respectively proportional and inversely proportional to the distances being apart from the edges of the uniform resistive surface 520. That is, the sizes of the compensating elements 540 beside the both ends of the uniform resistive surface 520 are smaller than those at the middle of the uniform resistive surface 520, but the intervals among the compensating elements 540 beside the both ends are wider than those at the middle. By doing so, the bow equipotential lines generated by the orthogonal electrical fields mentioned above can be compensated. Further, the relationships between the sizes of the compensating elements 540 and the interval distances among thereof are now described in details as following:  $LC_n = ( ( n * ( ( DA / LA ) * RG + RL ) * C ) / DB ) - LC_0$ , where  $n$  represents the compensated section number,  $LC_n$  represents the compensated width of the  $n^{th}$  section (unit: inch),  $DA$  represents the line distance of each section of silver paste (unit: inch),  $LA$  represent the contact length between each section of silver paste and ITO (unit: inch),  $RG$  represent the glass surface resistance ~~(unit: ohm)~~(unit: ohm/inch<sup>2</sup>),  $RL$  represents the line resistance of each section of silver paste ~~(unit: ohm)~~(unit: ohm/inch),  $C$  represents an adjust constant (about 45.3),  $DB$  represents the distance of silver paste pattern (unit: inch), and  $LC_0$  represents the width (a known value) of the  $0^{th}$  section (unit: inch). In addition, principally, the material of the plurality of compensating elements 540 and the material of the uniform resistive surface 520 are the same. The plurality of

compensating elements 540 are formed during an etching process of the uniform resistive surface 520 removing the blocks 540'.